

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Koji SHIGEMATSU

Group Art Unit: Not yet Assigned

Application No.: Rule 53(b) Division of Application
No. 09/234,969

Examiner: Not yet Assigned

Filed: November 28, 2000

Docket No.: 105192.01

For: PROJECTION OPTICAL SYSTEM AND EXPOSURE APPARATUS AND METHOD

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

Prior to initial examination on the merits, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 1-15, 19-30 and 33-37 without prejudice or disclaimer.

Please amend claims 16, 17, 31, 32 and 38 as follows:

16. (Amended) A method of patterning a photosensitive workpiece with a pattern present on a reticle, the method comprising the steps of:

- a) illuminating the reticle;
- b) projecting light from said reticle with [the] a projection optical system,

[as set forth in claim 1] said projection optical system including, along an optical axis:

- i) a first lens group having positive refractive power,
- ii) a second lens group having negative refractive power,

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